EAST Search History

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L1	2093	(process\$3 or method or manufactur\$3 or fabricat\$3 or form \$3 or mak\$3 or made) near5 (\$3PSM or (phas\$3 or shift\$3) near3 (mask or photomask or reticle)).clm.	US- PGPUB; USPAT	ADJ	ON	2009/02/25 12:29
L2	222632	(opaque or absorber or absorber or absorbing or chromium or chrome or "Cr" or (light or lighted or lighting or radiation or radiant or irradiation or expose or exposure or exposed or exposing) near3 (block or blocker or blocked or blocking or dark or darkened or darkening or shade or shaded or shading or reduced or reduced or reduced or decrease or decreased or decreasing)).clm.	US- PGPUB; USPAT	ADJ	ON	2009/02/25 12:32
L3	4518	((transparent or substrate or support or base or silica or quartz or glass) and (etch or etched or etching) and (rectangle or rectangular or square)).clm.	US- PGPUB; USPAT	ADJ	ON	2009/02/25 12:35

L4	698283	((continue or continuous or extend or extended or extended or extended or enlarged or enlarged or enlarging or (un or non) (interrupt or interrupted or interrupting or broken or broke or break or divide or divided or dividing or separated or separated or separating) or ("not" or non) (interrupt or interrupting or broken or broke or break or divide or divided or dividing or separate or separate or separate or separate or separate or separate or separated or separating)) near3 (surface or shape or plane or region or area or portion or element or structure)).clm.	US- PGPUB; USPAT	ADJ	ON	2009/02/25
L5	2877	((vertically or vertical) near3 (align or aligned or alignment or (line or lined or ligning) up or register or registered or registration) and (pattern or patterning or resist or photoresist or developed or developing)).clm.	US- PGPUB; USPAT	ADJ	ON	2009/02/25 12:51
L6	0	1 and 2 and 3 and 4 and 5	US- PGPUB; USPAT	ADJ	ON	2009/02/25 12:53

2/25/09 12:53:53 PM

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